ABSTRACT

A reaction chamber (100) and a reaction device (200) are disclosed. The reaction chamber (100) includes a hollow heating member (20), a rotating platform, a protection plate assembly and a separator (70). The rotating platform is rotatably provided in an inner cavity (201) of the hollow heating member (20). The rotating platform is used for bearing a wafer. The protection plate assembly is provided on two sides of the rotating platform. The separator (70) is erected on the protection plate assembly. The separator (70) is matched with the protection plate assembly.

(To be published with Fig. 5)